L Number	Hits	Search Text	DB	Time stamp
-	79	first\$ near10 (HF or fluoric) same (ozone or "o.sub.3" or "o3")	USPAT;	2003/12/08
		or "6. sub. 3" or "63")	US-PGPUB; EPO; JPO; DERWENT; IBM TDB	16:25
-	3	first\$ near10 (HF or fluoric) same (ozone or "o.sub.3" or "o3") same HCl	USPAT; US-PGPUB; EPO; JPO;	2003/12/03 15:40
	2	20010003680.pn.	DERWENT; IBM_TDB USPAT; US-PGPUB;	2003/12/03
_	15	"1005072"	EPO; JPO; DERWENT; IBM_TDB USPAT;	2003/12/03
_	298	(WF or fluoria) game (egene on the sub 21	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	15:42
	290	(HF or fluoric) same (ozone or "o.sub.3" or "o3") same hcl	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03
_	45	(HF or fluoric) same (ozone or "o.sub.3" or "o3") same hcl same wafer	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03
-	81	(HF or hydrofluoric or fluoric) same (ozone or "o.sub.3" or "o3") same hcl same treat\$	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 16:29
-	54	(HF or hydrofluoric or fluoric) same (ozone or "o.sub.3" or "o3") same hol and 438/\$.ccls.	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 16:33
-	92	(HF or hydrofluoric or fluoric) same (ozone or "o.sub.3" or "o3") same sequen\$	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 16:33
-	58	(HF or hydrofluoric or fluoric) near20 (ozone or "o.sub.3" or "o3") same sequen\$	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 16:42
-	131	(ozone or "o.sub.3" or "o3") same (hcl or hydrochloric) same sequen\$	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 16:42
_	245	(Ozone or "o.sub.3") same (hcl or hydrochloric) and 438/\$.ccls.	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/08 16:26
-	23	(Ozone or "o.sub.3") same (hcl or hydrochloric) same rins\$ and 438/\$.ccls.	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/12/08 16:31
_	6	(Ozone or "o.sub.3") same (hcl or hydrochloric) same hydrophil\$ and 438/\$.ccls.	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/08 16:27

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_	102	(Ozone or "o.sub.3") same (hcl or	USPAT;	2003/12/08
		hydrochloric) same etch\$ and 438/\$.ccls.	US-PGPUB;	16:31
			EPO; JPO;	
			DERWENT;	
	1.0		IBM_TDB	
	48	(Ozone or "o.sub.3") same (hcl or	USPAT;	2003/12/08
		hydrochloric) same etch\$ and HF and 438/\$.ccls.	US-PGPUB;	16:35
		438/\$.CCIS.	EPO; JPO; DERWENT;	
			IBM TDB	
_	0	(Ozone or "o.sub.3") same (hcl or	USPAT;	2003/12/08
		hydrochloric) same etch\$ and HF and	US-PGPUB;	16:35
		438/734\$.ccls.	EPO; JPO;	1.0.00
		1117, 1117, 11111	DERWENT;	
			IBM TDB	
_	3	(Ozone or "o.sub.3") same (hcl or	USPĀT;	2003/12/08
		hydrochloric) and 438/734.ccls.	US-PGPUB;	16:36
		-	EPO; JPO;	
			DERWENT;	
			IBM TDB	
-	13	(Ozone or "o.sub.3") and (hcl or	USPAT;	2003/12/08
	1	hydrochloric) and 438/734.ccls.	US-PGPUB;	16:43
	1		EPO; JPO;	,
	1		DERWENT;	
			IBM_TDB	
_	42		USPAT;	2003/12/08
		hydrochloric) same follow\$4 and	US-PGPUB;	16:44
		438/\$.ccls.	EPO; JPO;	
	1		DERWENT;	
			IBM_TDB	
-	26		USPAT;	2003/12/08
		hydrochloric) same follow\$4 same solution	US-PGPUB;	16:50
		and 438/\$.ccls.	EPO; JPO;	
	1		DERWENT;	
	24	(3-3	IBM_TDB	
-	24	(hcl or hydrochloric) same solution same	USPAT;	2003/12/08
		hydrophil\$5 and 438/\$.ccls.	US-PGPUB;	16:54
			EPO; JPO;	
			DERWENT; IBM TDB	
_	381	(hcl or hydrochloric) same solution same	USPAT;	2003/12/08
]	oxide near4 (layer or film) and	US-PGPUB;	16:54
		438/\$.ccls.	EPO; JPO;	10.54
		100, 4.0015.	DERWENT;	
			IBM TDB	1
_	111	(hcl or hydrochloric) near10 etch\$4 same	USPAT;	2003/12/08
	1	solution same oxide near4 (layer or film)	US-PGPUB;	16:56
		and 438/\$.ccls.	EPO; JPO;	
	1		DERWENT;	1
			IBM TDB	1
	109	(hcl or hydrochloric) near10 etch\$4	USPAT;	2003/12/08
		near10 oxide near4 (layer or film) and	US-PGPUB;	17:01
		438/\$.ccls.	EPO, JPO;	[
			DERWENT;	1
			IBM_TDB	
-	78	(hcl or hydrochloric) near5 (solution or	USPAT;	2003/12/08
	1	acid) near10 etch\$4 near10 oxide near4	US-PGPUB;	17:11
		(layer or film) and 438/\$.ccls.	EPO; JPO;	
			DERWENT;	
		l	IBM_TDB	
-	99	(sequenc\$4 or sequent\$6) near10 clean\$4	USPAT;	2003/12/08
		same (ozone or "o.sub.3")	US-PGPUB;	17:11
			EPO; JPO;	
			DERWENT;	
		/	IBM_TDB	
-	26	(sequenc\$4 or sequent\$6) near10 clean\$4	USPAT;	2003/12/08
		same (ozone or "o.sub.3") same solution	US-PGPUB;	17:21
	1		EPO; JPO;	
			DERWENT;	
			IBM TDB	

	92	(sequenc\$4 or sequent\$6) same (ozone or "o.sub.3") same solution same (hcl or hydrochloric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/08 17:24
_	2	((sequenc\$4 or sequent\$6) same (ozone or "o.sub.3") same solution same (hcl or hydrochloric)) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/08
_	10	(sequenc\$4 or sequent\$6) same (ozone or "o.sub.3") same solution same (hcl or hydrochloric) same (etch\$ or clean\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:13
-	146590	(sequenc\$4 or sequent\$6) near4 process\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:16
-	7621	((sequenc\$4 or sequent\$6) near4 process\$5) and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:17
-	227	((sequenc\$4 or sequent\$6) near4 process\$5) and 438/\$.ccls. and (ozone and "o.sub.3")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:18
_	195	((sequenc\$4 or sequent\$6) near4 process\$5) and 438/\$.ccls. and (ozone or "o.sub.3") and (hcl or hydrochlor\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:18
-	51	((sequenc\$4 or sequent\$6) near4 process\$5) and 438/\$.ccls. and (ozone or "o.sub.3") same (hcl or hydrochlor\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:19
_	23	((sequenc\$4 or sequent\$6) near4 process\$5) same ("without" near5 rins\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/09 10:19